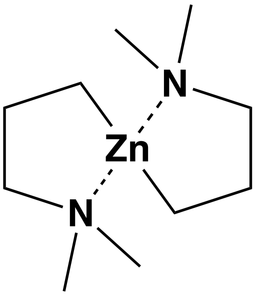

[Zn(DMP)$_2$]

Figure 1. Molecular structure of [ZnDMP$_2$]

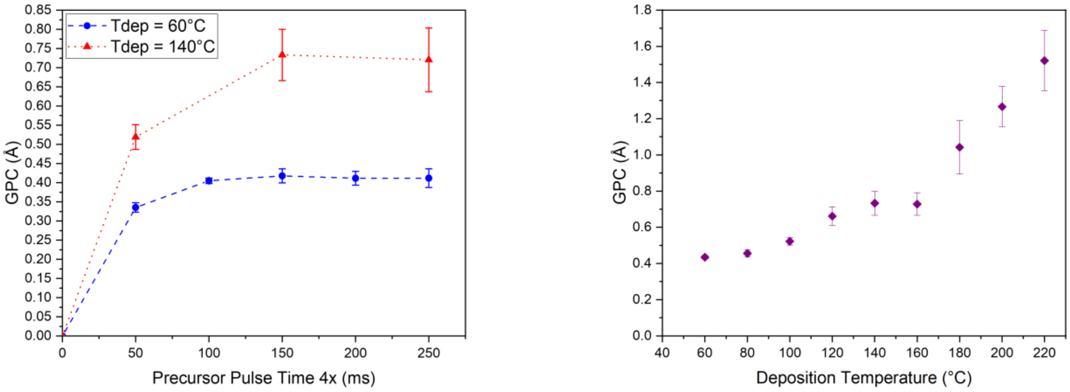

Figure 2. ALD characteristics of the PEALD process for ZnO on Si(100) employing [Zn(DMP)$_2$] as precursor: left) precursor saturation study at 60 and 140 °C; right) temperature dependency of the growth rate.

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